

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	110779	CMP or "chemical mechanical polishing"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 12:53
L2	45	(silica or "SiO. sub.2") same (oxalic or malic or malonic or acetic) same BTA	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 12:55
L3	552	(silica or "SiO. sub.2") and (oxalic or malic or malonic or acetic) and BTA and slurry	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 12:55
L4	426	(silica or "SiO. sub.2") same (oxalic or malic or malonic or acetic) same (BTA or chelating or complexing)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 12:56
L5	12	schroeder-david.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 13:06
L6	14	moeggenborg-kevin.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/06/30 13:06

6/30/09 1:07:28 PM

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